



Surface textured molybdenum zinc oxide for light diffusion enhancement

Ching-Ming Hsu^{*}, Hon-Bin Lin, Wen-Tuan Wu

Department of Electro-Optical Engineering, Southern Taiwan University, 1 Nan-Tai Street, Yung-Kang City, Tainan County, Taiwan 710, Republic of China

ARTICLE INFO

Article history:

Received 14 February 2008

Received in revised form 13 December 2008

Accepted 15 December 2008

Available online 25 December 2008

Keywords:

Molybdenum

Zinc oxide

Surface texture

Light trapping

ABSTRACT

Surface textures have been fabricated on a molybdenum doped zinc oxide (MZO) film using a shadow mask in a co-sputter process. The surface textures yielded 5.3% and 10.1% of light diffusion in the visible light region for MZO films with a thickness of 100 nm and 200 nm, respectively. Light diffusion in the near infra-red region was slightly less with 4.5% for the 100 nm MZO film and 8.9% for the 200 nm MZO film. The enhanced light diffusion will be beneficial to the light trapping efficiency of a-Si/ μ -Si based thin film solar cells.

© 2008 Elsevier B.V. All rights reserved.

1. Introduction

Transparent conductive oxides (TCO) with textured surfaces have been commonly used as electrodes in thin film solar cells [1–4]. The textured surface allows the incoming solar light to diffuse laterally into the thin film absorbers of a solar cell. Since the traveling length of the diffused light in the absorber layers is a number of magnitudes of order longer than that of the directly transmitting light, the light trapping efficiency would be largely enhanced and thus lead to the improved power efficiency. For amorphous (a-Si)/microcrystalline (μ -Si) based thin film solar cells, lateral light diffusion is particularly important because of the thin thickness required in a-Si (due to the light-induced degradation) and the low absorption efficiency in μ -Si [1]. Yielding textured surfaces is then crucial when employing TCO films to serve as a transparent conductive electrode in the a-Si/ μ -Si solar cells in addition to the basic requirements of high optical transparency and low electrical resistance.

Zinc oxide (ZnO) has been a highly noticed TCO material for the applications in thin film solar cells for its low cost, high optical transparency in the near infra-red region and good chemical stability during a-Si depositions [5–8]. Forming textured surfaces is inclusively one of the important issues when fabricating ZnO films. Several approaches have been proposed to obtain surface textures on ZnO films, including the direct growth by well-controlled chemical vapor deposition [9,10] and the post chemical etching [11,12]. Synthesis of optical grating patterns on film surfaces by photolithography technique has also been demonstrated to be able to perform surface diffusion effect [13,14]. These methods however employ processes of high cost such as photolithography patterning, or encounter the

problem of limited physical structure of surface textures when using direct growth or chemical etching.

In this article we proposed a method that could fabricate molybdenum (Mo) doped ZnO (MZO) films with surface textures of a desired geometry without additional post-treatments. This method employs a shadow mask attached to a substrate, which allows surface textures to form through the opening of the mask during film deposition. Since the physical dimension and the shape of the opening are defined directly on the shadow mask, surface textures with a well-controlled geometry are obtainable. The optical diffusion effect caused by the textured surface of ZnO films was investigated. The effect of MZO thickness and MZO film/texture interface to the optical diffusion was also discussed.

2. Experimental details

A molybdenum doped ZnO film with a thickness of 100 nm or 200 nm was first deposited on a 50 mm×50 mm glass substrate at 300 °C using a magnetron co-sputter approach as illustrated in Fig. 1. Mo was sputtered with a dc power of 10 W whereas ZnO with an rf power of 150 W. The substrate was placed 10 cm above the sputter sources and was rotated at a speed of 15 rpm. The concentration of Mo was controlled by the opening area of a slit shutter located in front of the Mo sputter source. On the MZO film, round surface textures were formed by the deposition of MZO through a metallic shadow mask that was attached to the substrate. The samples were then annealed in vacuum at 350 °C for 1 h to enhance the electrical and optical properties of the MZO films.

MZO films with four types of geometrical structures were fabricated, (a) 100 nm, (b) 100 nm with surface textures, (c) 200 nm and (d) 200 nm with surface textures. These films were characterized by energy dispersive X-ray analysis using Hitachi S4100-EDS for Mo

^{*} Corresponding author. Tel.: +886 6 2533131x3360; fax: +886 6 2432912.

E-mail address: tedhsu@mail.stut.edu.tw (C.-M. Hsu).

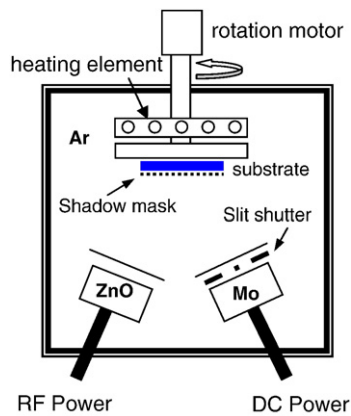


Fig. 1. Schematic of a co-sputter apparatus for fabricating surface textured MZO film.

concentration at acceleration voltage of 15 kV and collection time of 60 s. Thickness was measured using surface profilometry (ET-4000 α -step). Optical transmittance was measured using Hitachi UV 3310 and the 4-point probe method was used for obtaining the sheet resistivity (4 Dimensions 280SI).

3. Results and discussions

3.1. Electrical and optical properties of MZO films

The lowest sheet resistivity of the MZO film in this study was $3.2 \times 10^{-3} \Omega \text{ cm}^2$, which was obtained from the film with 1.85 wt.% concentration of Mo and after thermal annealing. Since the goal of this work was to investigate the optical diffusion by MZO surface textures, the electrical performance of the MZO film was not further improved. Surface textures were then only processed on top of the MZO film with this optimal sheet resistivity. The following discussions will mainly focus on the optical effects caused by the MZO surface textures.

Fig. 2 shows the optical spectra of MZO films in the wavelength region from 350 nm to 1100 nm. The measurement was conducted with light incident from the glass side at normal angle to the sample. It can be seen that in the entire wavelength region MZO films with surface textures (type (b) and (d)) performed lower optical transmit-

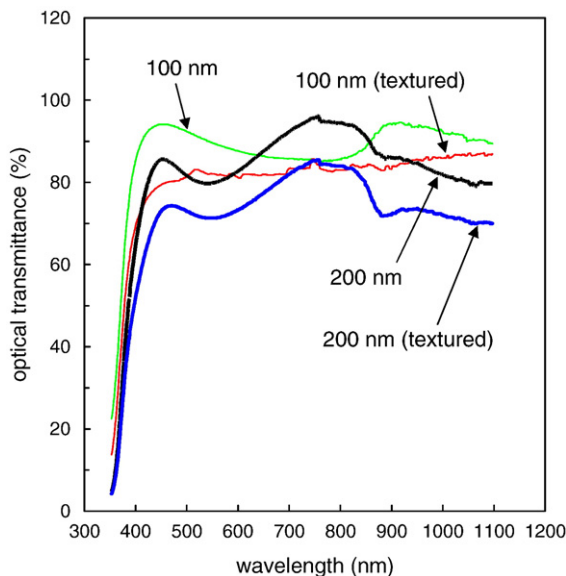


Fig. 2. Optical spectra of MZO films with various physical structures in the wavelength region from 350 to 1100 nm.

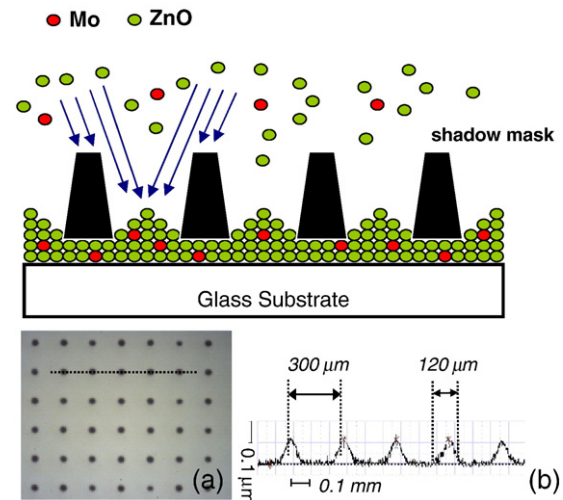


Fig. 3. (a) optical microscope image; (b) a-step profile of the surface textured MZO film. Above shows the shadowing effect of the shadow mask.

tance than the plain MZO films (type (a) and (c)). Clearly the causes of the drop in the optical transmittance are related with the MZO textures fabricated on the MZO films. We examined the morphology of these textures and analyzed the possible causes how they influence the optical behavior of the incident light.

3.2. Physical dimensions of MZO films

Fig. 3(a) and (b) show the optical microscope image and α -step profile of the surface textured MZO film, respectively. The dark spots in Fig. 3(a) represent where the MZO textures locate. These textures are nearly identical and spread evenly on the MZO film, suggesting a well controlled and periodic texture pattern can be formed with the shadow mask approach. Above the figures schematically illustrates how these textures are formed by the shadowing effect of the metallic shadow mask. Observed from the a-step profiling in Fig. 3(b), these textures appear in spherical shape and are 300 μm pitched to each other. The MZO texture was measured to have physical dimensions of

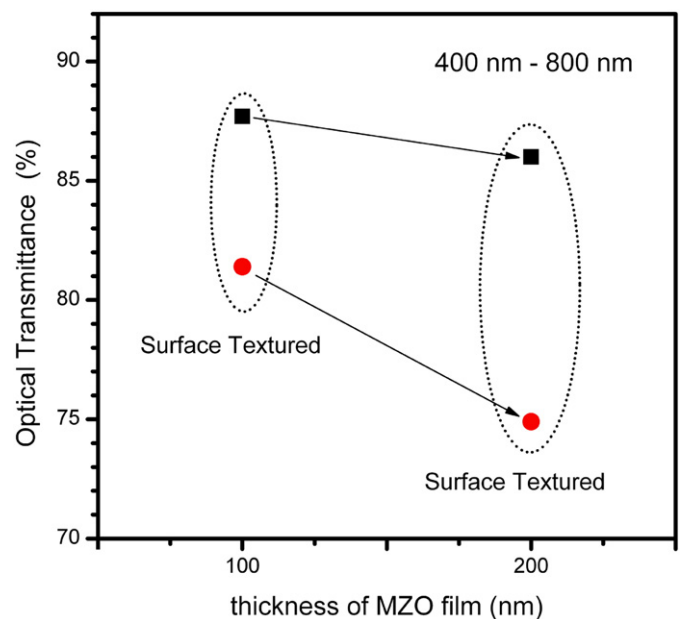


Fig. 4. Averaged optical transmittance of MZO films with various physical structures in the visible light region from 400 to 800 nm.

Download English Version:

<https://daneshyari.com/en/article/1671943>

Download Persian Version:

<https://daneshyari.com/article/1671943>

[Daneshyari.com](https://daneshyari.com)